

RF-2.75 Plasma Source

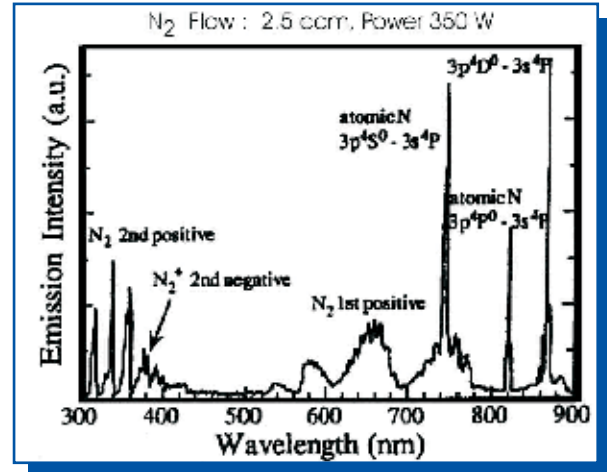


Description

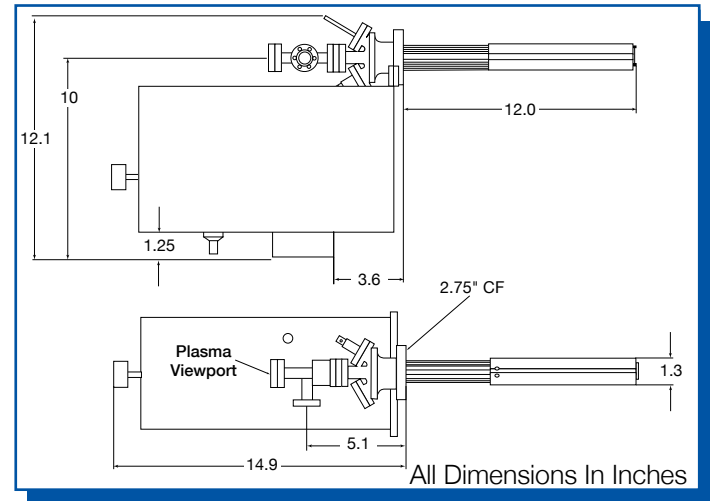
- The RF-2.75 Compact RF Plasma Source is excellent for oxide and nitride deposition.
- The RF Plasma Source and manually tuned RF matching network mounts to a standard 2.75" CF (70 mm) Flange.
- Equipped with an optical viewport, the RF-2.75 Plasma Source is fully compatible with SVT Associates' RoboRF Automation Software.
- The integrated charge suppression ensures that ions do not reach the target and also eliminates substrate damage due to unintentional sputtering.

Features

- Compact Design
- Integrated Charge Suppression
- Automatic Tuning Network Available
- Optical Port for Plasma Monitoring
- Integral Water Cooling
- Custom Plasma Chamber and Aperture Available



Nitrogen Plasma Emission Spectra of the SVTA-RF-2.75 Plasma Source



Specifications

RF Power Level	150 – 400 Watts
Gas Flow Rate	0.1 – 5 SCCM
Flange	2.75" CF
Source Diameter	1.30"
Water Cooling	0.17 GPM Flow Rate
RF Matching Network	Manually Tuned
Plasma Chamber	PBN, Alumina, or Quartz

Models	Description
SVTA-RF-2.75PBN	PBN, 0.11" Aperture
SVTA-RF-2.75ALO	Alumina, 0.11" Aperture
SVTA-RF-2.75Q	Quartz, 0.11" Aperture

